

FIG. 1

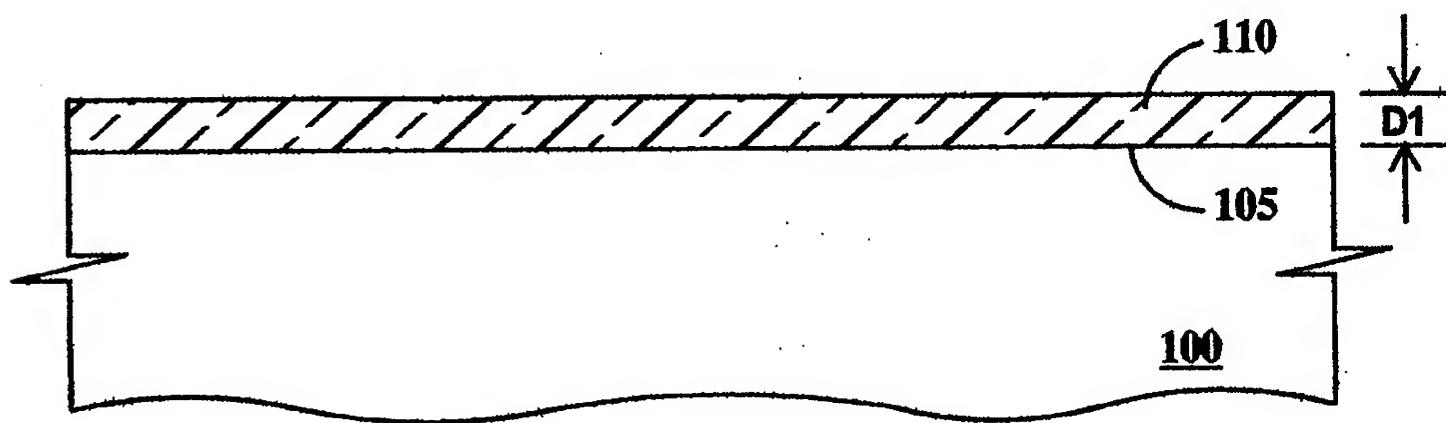


FIG. 2

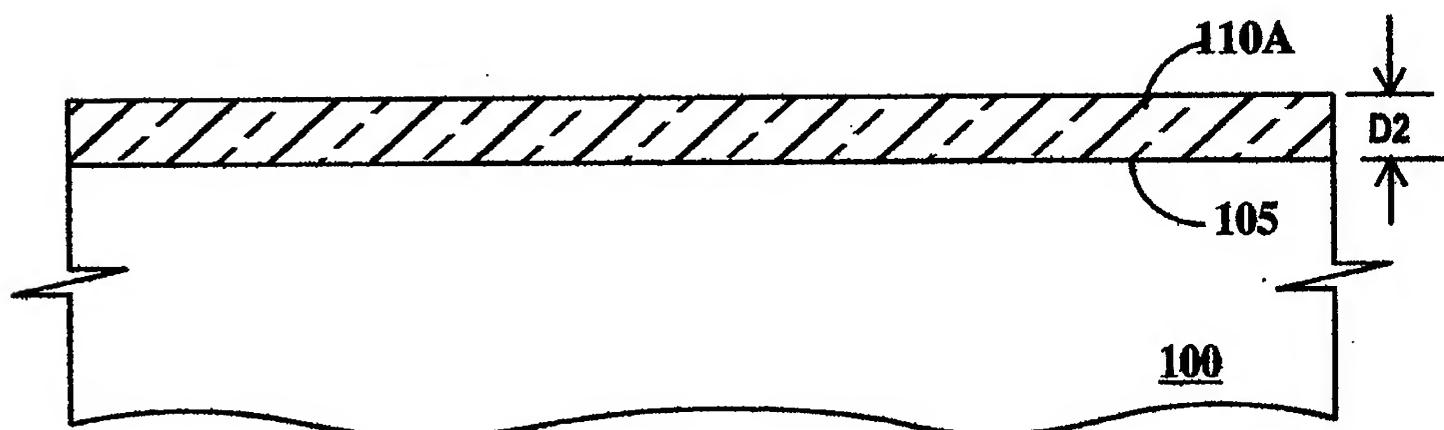
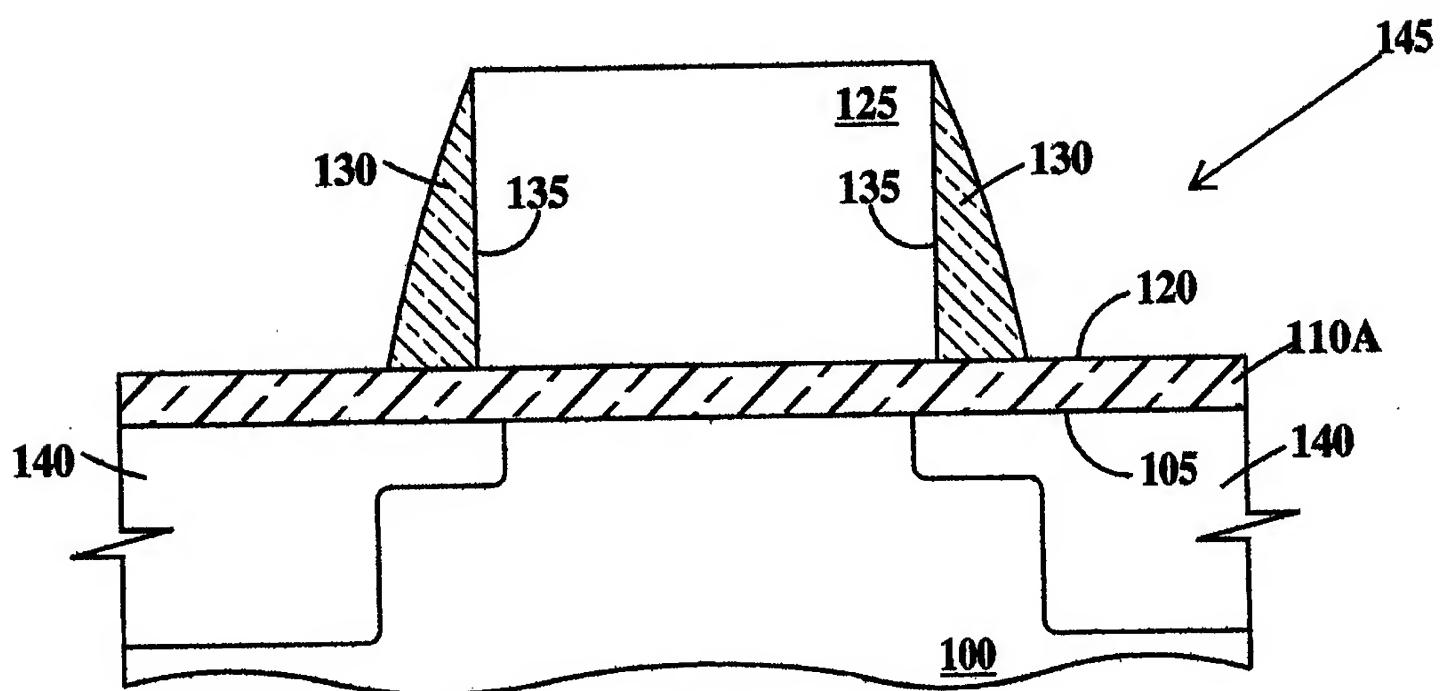
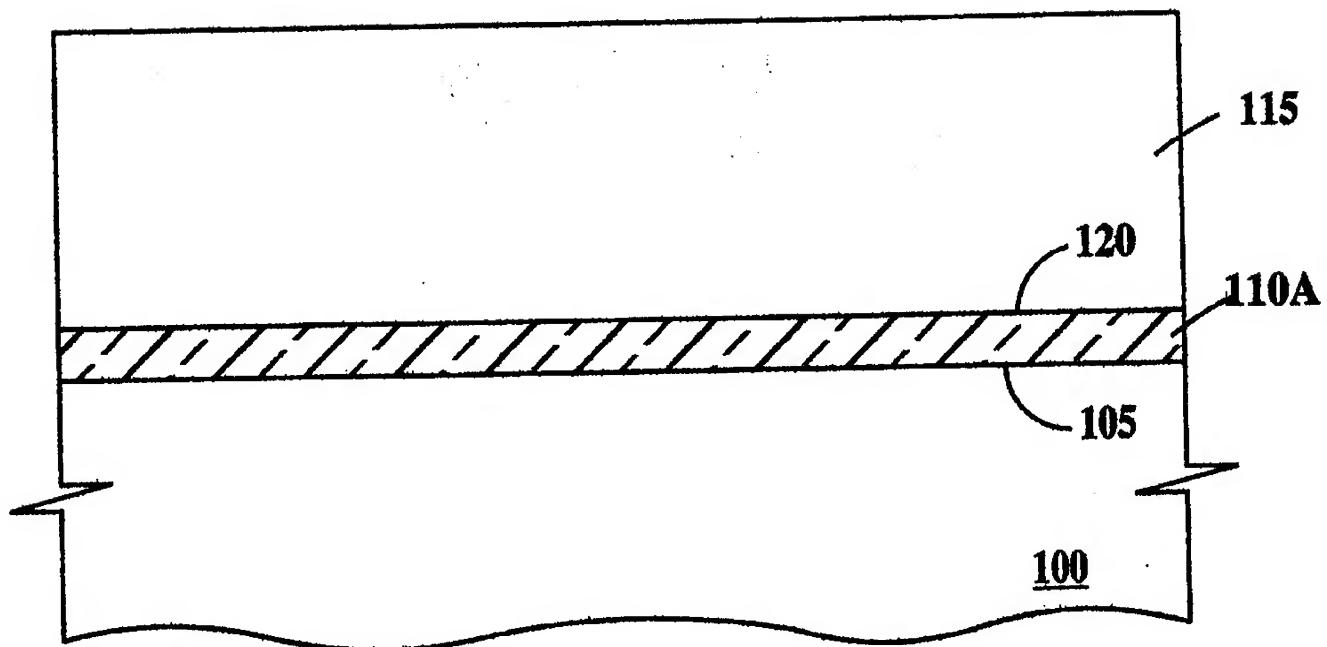


FIG. 3



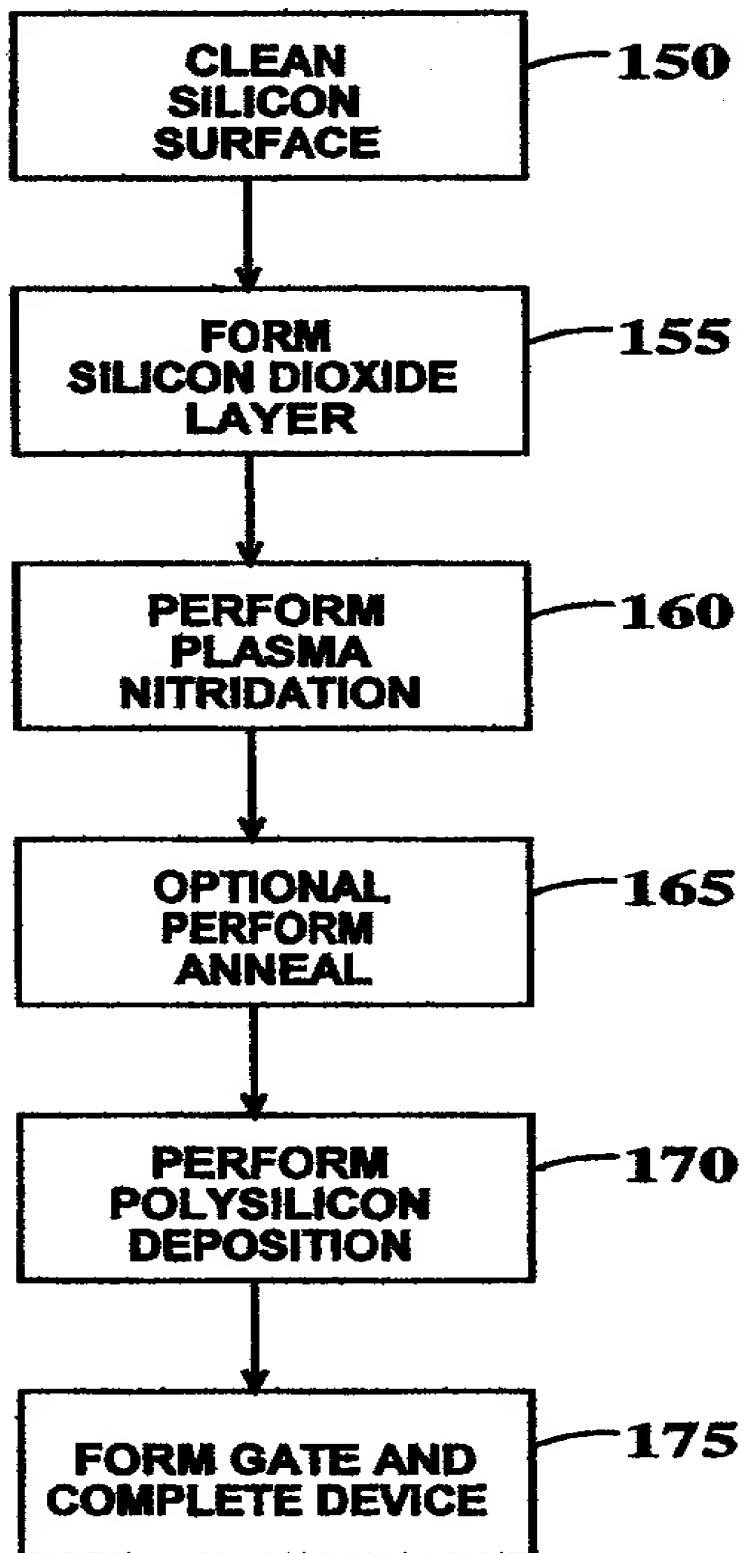


FIG. 6

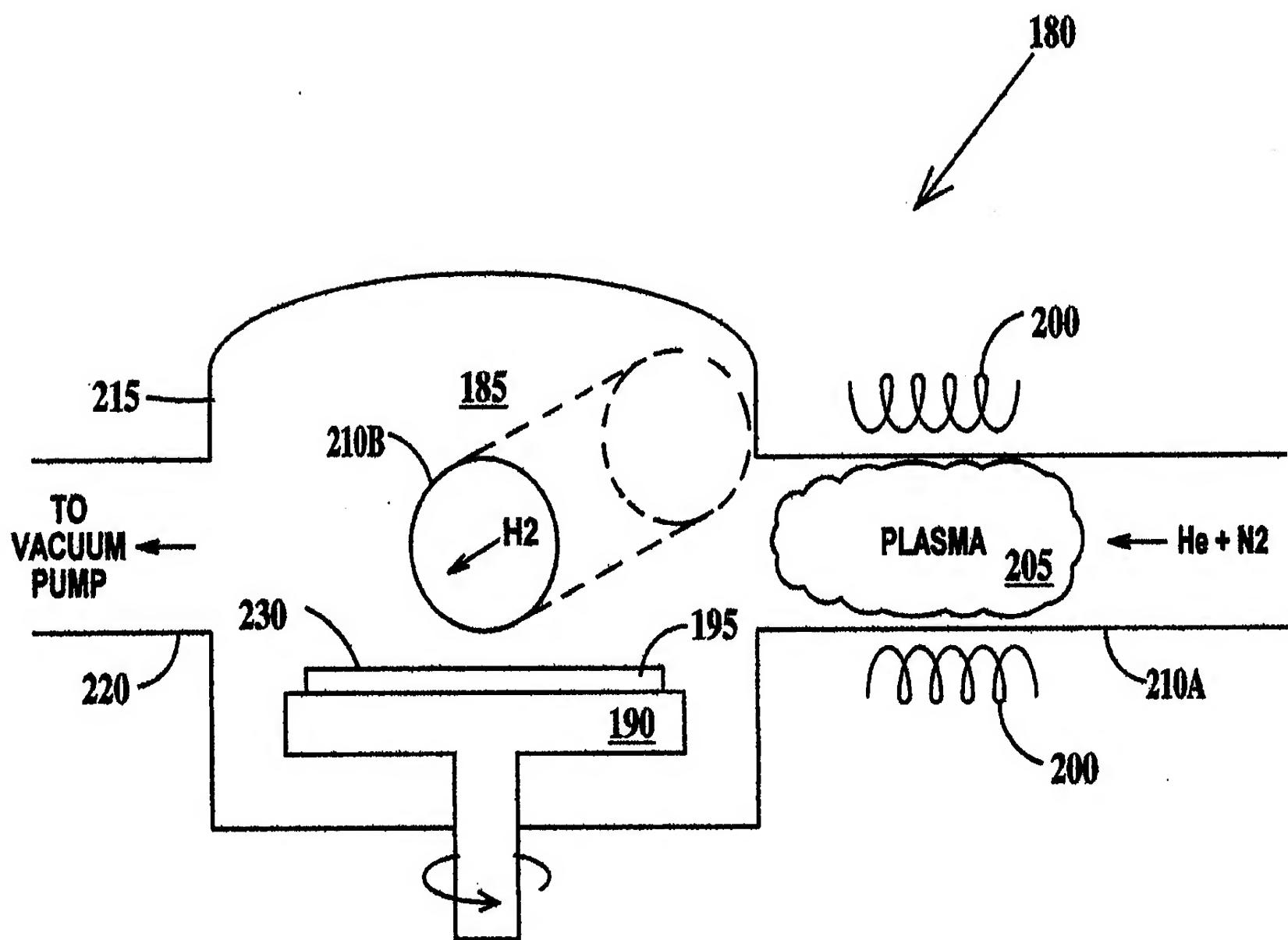


FIG. 7

ACROSS WAFER THICKNESS UNIFORMITY
POST REMOTE PLASMA NITRIDATION

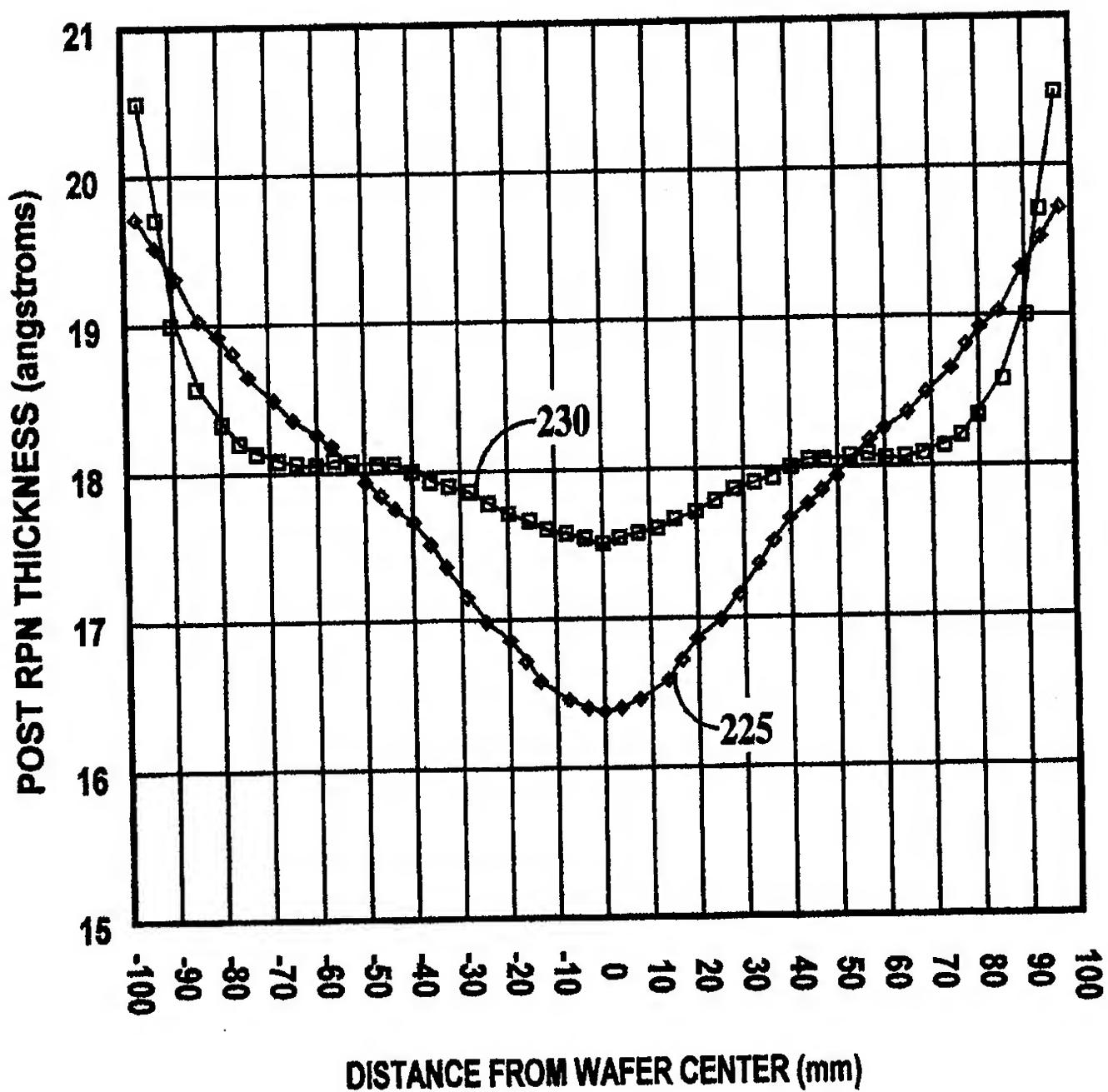


FIG. 8

ACROSS WAFER THICKNESS UNIFORMITY
POST REMOTE PLASMA NITRIDATION
ON NATIVE OXIDE

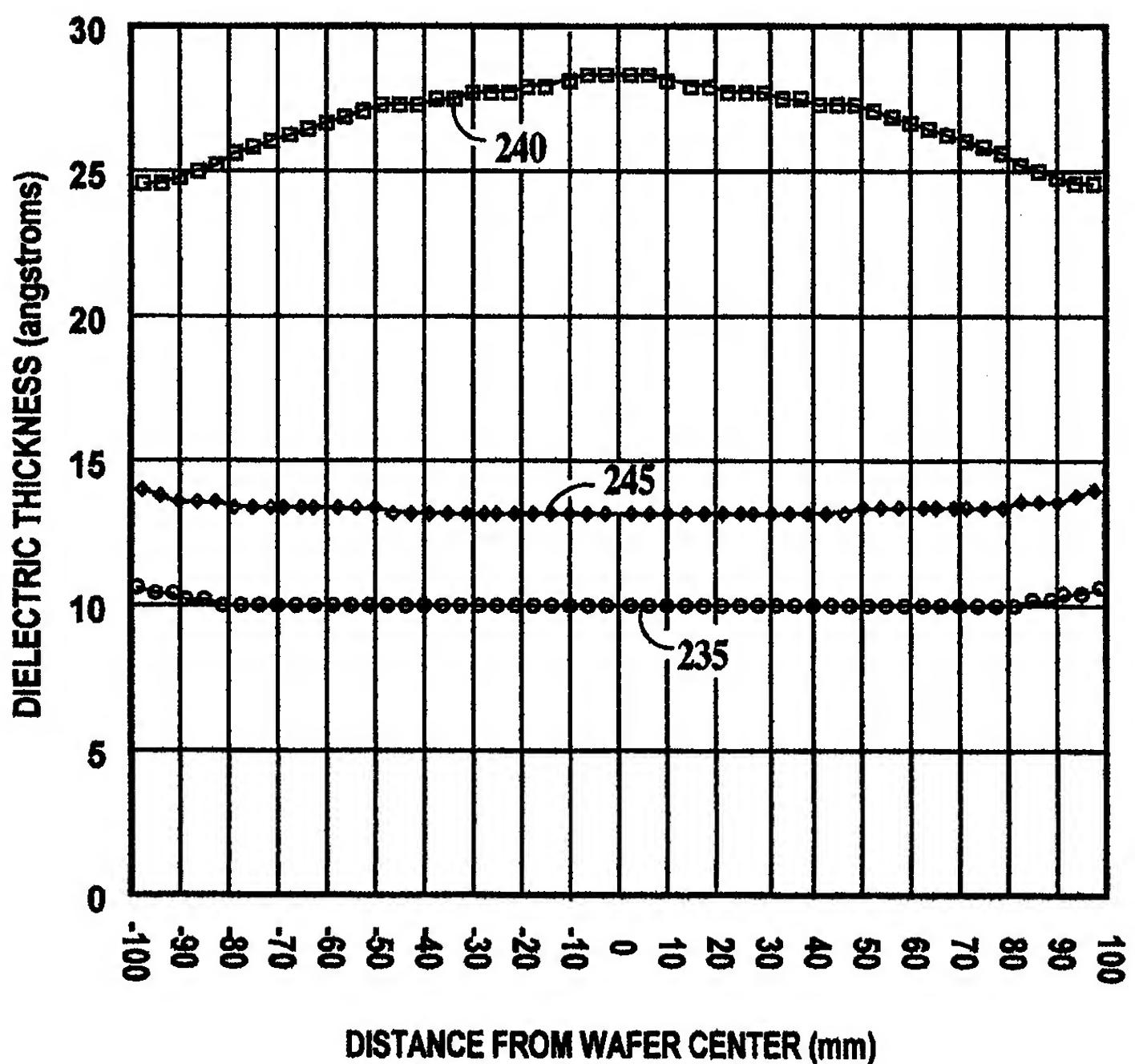


FIG. 9

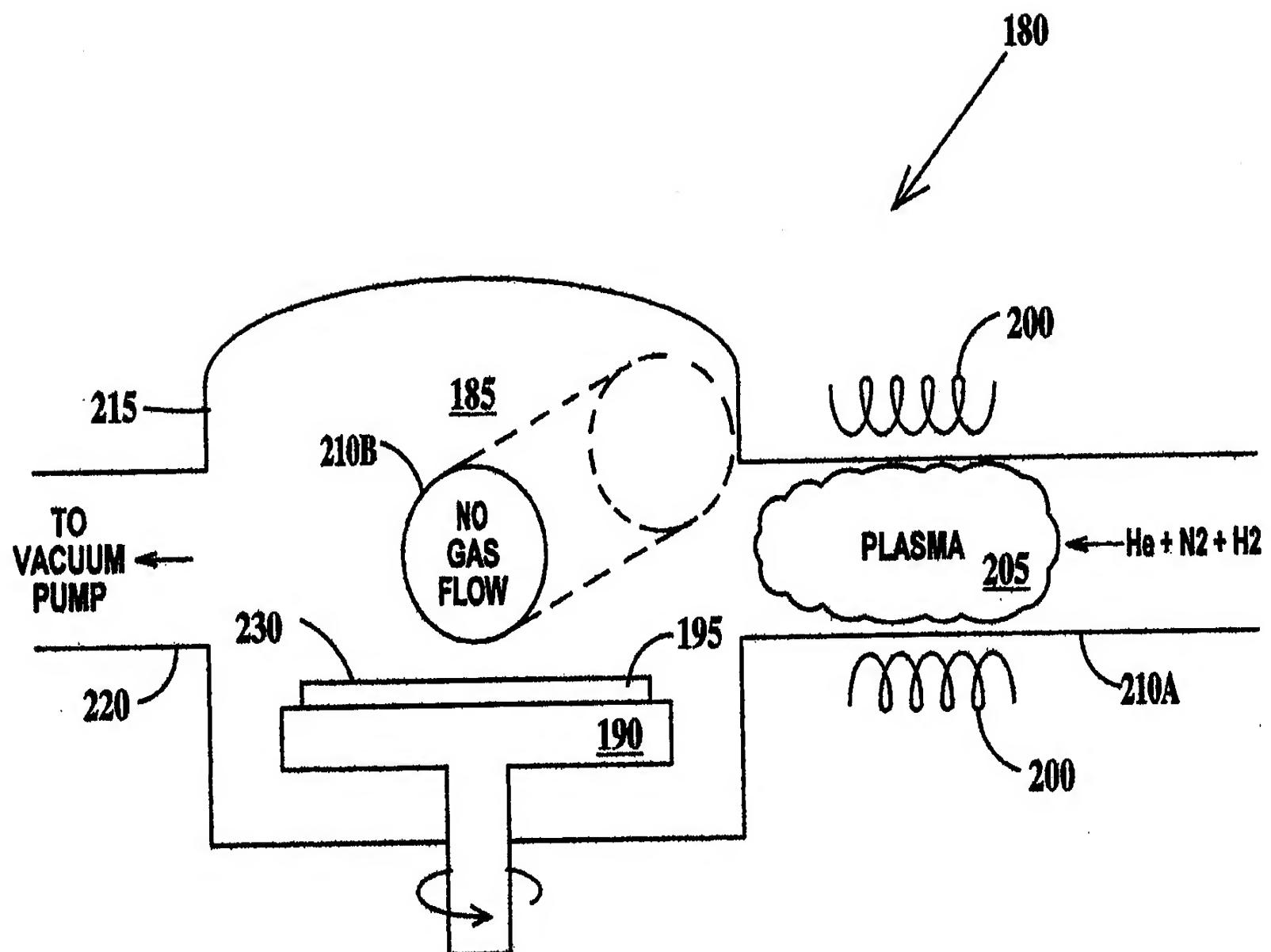


FIG. 10